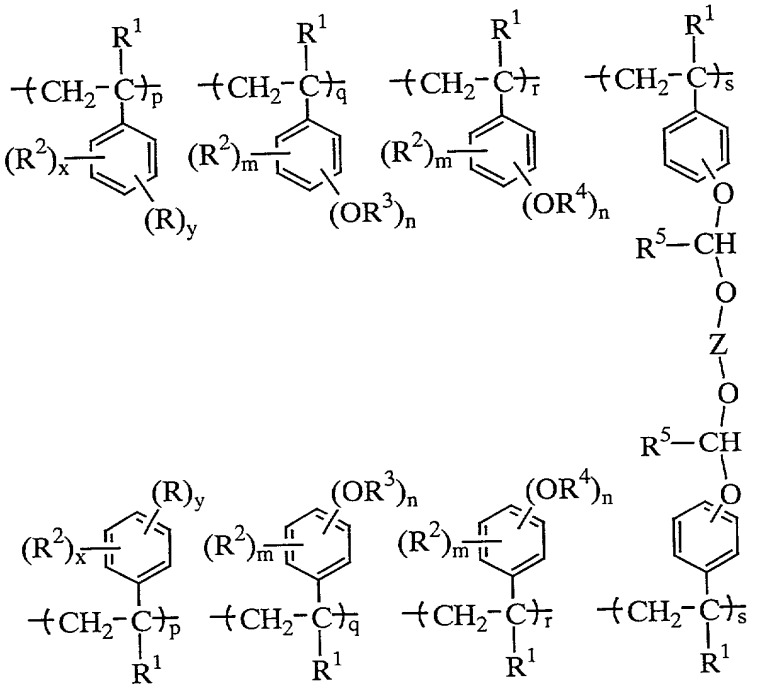
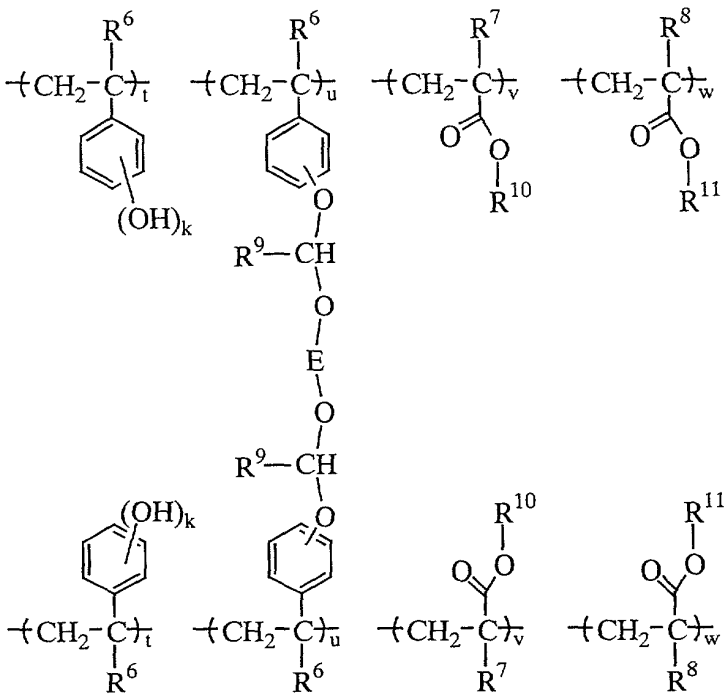
CLAIMS:

1. A chemical amplification type resist composition comprising a polymeric mixture of a polymer comprising recurring units of the general formula (1) and having a weight average molecular weight of 1,000 to 500,000 and a polymer comprising recurring units of the general formula (2) and having a weight average molecular weight of 1,000 to 500,000,



(1)

wherein R is a hydroxyl group or a OR^3 group, R^1 is hydrogen or methyl, R^2 is a straight, branched or cyclic alkyl group of 1 to 8 carbon atoms, R^3 and R^4 each are an acid labile group, R^5 is methyl or ethyl, Z is a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms, x is 0 or a positive integer, y is a positive integer, satisfying $x+y \leq 5$, m is 0 or or a positive integer, n is a positive integer, satisfying $m+n \leq 5$, p, q, r and s each are 0 or a positive number, satisfying $p+q+r+s = 1$,



(2)

wherein R^6, R^7 and R^8 each are hydrogen or methyl, R^9 is methyl or ethyl, E is a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms, R^{10} is a straight, branched or cyclic alkyl group of 1 to 20 carbon atoms, which may contain an oxygen or sulfur atom, R^{11} is a tertiary alkyl group of 1 to 20 carbon atoms, k is 0 or a positive integer of up to 5, t and w each are a positive number, u and v each are 0 or a positive number, either one of u and v is not equal to 0, satisfying t+u+v+w = 1.

2. A chemical amplification type, positive resist composition comprising

(A) an organic solvent,

(B) the polymeric mixture of claim 1 as a base resin, and

(C) a photoacid generator.

3. A chemical amplification type, positive resist composition comprising

(A) an organic solvent,

(B) the polymeric mixture of claim 1 as a base resin,

(C) a photoacid generator, and

(D) a dissolution regulator.

4. The resist composition of claim 2 or 3, further comprising (E) a basic compound.